

Time allowed: 3 Hours

Max. Marks: 50

NOTE: Attempt five questions in all, including Question No. 1 which is compulsory and selecting two questions from each Section. Use of scientific calculator is allowed.

X-X-X

Q1. Answer the following:-

- What will be amount of current flowing between source and drain region of MOSFET when depletion region width on drain and source side is equal? (2)
- Design 2-bit multiplexer using MOS transistors. (2)
- Which is better and why – CMOS NAND gate or CMOS NOR gate? (2)
- What is the effect on depletion charge density, oxide potential if body of n-channel MOS capacitor is connected to a positive power supply? (2)
- Why MOSFET is not used in accumulation region, even charge carriers are present in channel? (2)

SECTION A

- Design the Full adder circuit using CMOS transmission gate. (5)
  - Derive equation for the gain of Resistive Load Inverter and discuss effect of transconductance. (5)
- Derive MOSFET current equation in different regions of operations. (5)
  - Why conventional MOSFET is not preferred beyond 32 nm technology? Discuss limitations in detail. (5)
- Design a resistive-load inverter with  $R = 1 \text{ k}\Omega$ , such that  $V_{OL} = 0.6 \text{ V}$ . The enhancement-type nMOS driver transistor has the parameters:  $V_{DD} = 5.0 \text{ V}$ ,  $V_{T0} = 1.0 \text{ V}$ ,  $\gamma = 0.2 \text{ V}^{1/2}$ ,  $\lambda = 0$ ,  $\mu_n C_{ox} = 22.0 \text{ }\mu\text{A/V}^2$ 
    - Determine the required aspect ratio,  $W/L$ . (5)
    - Determine  $V_{IL}$  and  $V_{IH}$ . (5)
  - Discuss the problems associated with linear load MOS inverter and how those problems are resolved by depletion load MOS Inverter? Draw load characteristic of depletion load MOS Inverter. (5)

SECTION B

- Derive equation for the low noise margin of a CMOS inverter. (5)
  - Discuss applications and limitations of BiCMOS transistors. (5)
- A pMOS transistor was fabricated on an n-type substrate with a bulk doping density of  $N_D = 10^{16} \text{ cm}^{-3}$ , gate doping density (n-type poly) of  $N_D = 10^{20} \text{ cm}^{-3}$ ,  $Q_p/q = 4 \times 10^{10} \text{ cm}^{-3}$  and gate oxide thickness of  $t_{ox} = 0.1 \text{ }\mu\text{m}$ . Calculate the threshold voltage at room temperature for  $V_{SB} = 0$ ,  $V_{GS} = 1.5 \text{ V}$  and  $V_{DS} = 3 \text{ V}$ . Use  $\epsilon_{si} = 11.7 \epsilon_0$ . (5)
  - Discuss and draw the CMOS AOI realization of the JK latch circuit. How the output toggles in this JK latch configuration? (5)
- Rise time of CMOS inverter is higher than fall time if aspect ratios of the nMOS and pMOS transistor are same, why? (2)
  - Preferred channel width of pMOS is 2.5 times higher than nMOS in CMOS inverter, why? (3)
  - A nMOS transistor has parameters  $W=10\text{ }\mu\text{m}$ ,  $L=1\text{ }\mu\text{m}$ , channel length modulation parameter is  $0.024 \text{ V}^{-1}$ ,  $t_{ox}=8 \text{ nm}$ ,  $V_{T0}=0.6 \text{ V}$ ,  $N_a=5 \times 10^{15} \text{ cm}^{-3}$ . Calculate the drain current for  $V_{SB} = 0$ . (5)

X-X-X